

197. B.M. Lum, A.R. Neureuther, B. La Fontaine, A.A. MacDowell, and O.R. Wood, II, "Validation of Modeling Hoechst AZ PN114 for EUV Projection Lithography and Evidence of Diffusion Effects on Resolution," OSA EUV Proceedings Vol. 23, pp. 184-192, 1994.
198. Wang and A.R. Neureuther, "Efficient and Innovative Use of Three-Dimensional Geometry Services in IC Topography Simulation," International Symposium on VLSI Technology, Systems, and Applications (VLSI-TSA), Taipei, Taiwan, ROC, June 1995
199. Andrew R. Neureuther, "Processing Issues and Modeling", SPIE Proceedings Vol. TTS4, Technologies for Microlithography Manufacturing, ISBN 0-8194-2009-3, pp. 58-133, 1996.
200. R. Socha, M. Yeung, A.R. Neureuther, R. Singh, "Models for Characterizing Phase-Shift Defects in Optical Projection Printing," IEEE Transactions on Semiconductor Manufacturing, Vol. 8, No 2, pp. 139-149, 1995.